## Ragava Lokasani

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/1439454/publications.pdf

Version: 2024-02-01

		1684188	1474206
16	83	5	9
papers	citations	h-index	g-index
1.6	1.6	1.6	77
16	16	16	77
all docs	docs citations	times ranked	citing authors

#	Article	IF	CITATIONS
1	Soft X-ray spectral analysis of laser produced molybdenum plasmas using the fundamental and second harmonics of a Nd:YAG laser. Optics Express, 2019, 27, 33351.	3.4	2
2	Soft x-ray spectral analysis of samarium plasmas produced by solid-state laser pulses. Journal of Physics B: Atomic, Molecular and Optical Physics, 2018, 51, 215001.	1.5	6
3	Characteristics of soft x-ray and extreme ultraviolet (XUV) emission from laser-produced highly charged rhodium ions. Journal of Applied Physics, 2018, 123, 183301.	2.5	1
4	Source development for extreme ultraviolet lithography and water window imaging. AIP Conference Proceedings, 2017, , .	0.4	2
5	XUV generation from the interaction of pico- and nanosecond laser pulses with nanostructured targets. Proceedings of SPIE, 2017, , .	0.8	O
6	Enhancement of extreme ultraviolet emission from laser irradiated targets by surface nanostructures. Laser and Particle Beams, 2017, 35, 574-578.	1.0	2
7	High ionization states observed in soft x-ray spectra from plasmas of second row transition elements produced by femtosecond laser pulses. Journal of Physics B: Atomic, Molecular and Optical Physics, 2017, 50, 145001.	1.5	2
8	Soft X-ray emission from molybdenum plasmas generated by dual laser pulses. Applied Physics Letters, 2016, 109, .	3.3	21
9	XUV spectra of 2nd transition row elements: identification of 3d–4p and 3d–4f transition arrays. Journal of Physics B: Atomic, Molecular and Optical Physics, 2015, 48, 245009.	1.5	11
10	Laser-Produced Plasma Spectroscopy of Medium to High-Z Elements in the 2 to 9 nm Spectral Region. Journal of Physics: Conference Series, 2015, 635, 092090.	0.4	0
11	Spectroscopy for identification of plasma sources for lithography and water window imaging. Journal of Physics: Conference Series, 2015, 635, 012026.	0.4	3
12	Spectroscopy for identification of plasma sources for lithography and water window imaging. Journal of Physics: Conference Series, 2015, 635, 092037.	0.4	0
13	Sources for beyond extreme ultraviolet lithography and water window imaging. Physica Scripta, 2015, 90, 054002.	2.5	24
14	Spectra of plasmas of Ru, Rh, Pd and Mo produced with nanosecond and picosecond laser pulses. , $2015,  ,  .$		1
15	Relationship between resist related outgassing and witness sample contamination in the NXE outgas qualification using electrons and EUV., 2013,,.		3
16	Assessment of Challenges in EUV Resist Outgassing and Contamination Characterization. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2012, 25, 609-616.	0.3	5